



Docket No. MIT7941

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

Applicants: Yong-Pil Han et al.  
Serial No.: 09/498,303  
Filed: February 4, 2000  
For: HF VAPOR PHASE WAFER CLEANING AND OXIDE ETCHING

Group Art Unit: 1763  
Examiner: T. Dang

#7A  
7/18/02  
NW

THE ASSISTANT COMMISSIONER FOR PATENTS  
WASHINGTON, DC 20231

I hereby certify under 37 CFR 1.8(a)  
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*Kenneth J. Ober*  
*July 18, 2002*

**AMENDMENT AND RESPONSE**

This is in reply to the Examiner's Action mailed March 13, 2002. A petition for a one-month extension of the statutory period for reply accompanies this response.

**Amendments:**

**In the Specification:**

Please amend the paragraph at p. 16, lines 15-19 as shown in the accompanying marked-up and clean version of this paragraph.

Please amend the paragraph at p. 23, lines 10-20 as shown in the accompanying marked-up and clean version of this paragraph.

**In the claims:**

Please amend claims 6, 9, 10, 15, 23, and 24 as shown in the accompanying marked-up and clean versions of these claims.